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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/707,081	11/20/2003	Shih-Chieh Kao	10585-US-PA	1080
31561	7590	11/17/2005	EXAMINER	
JIANQ CHYUN INTELLECTUAL PROPERTY OFFICE 7 FLOOR-1, NO. 100 ROOSEVELT ROAD, SECTION 2 TAIPEI, 100 TAIWAN			KORNAKOV, MICHAIL	
		ART UNIT	PAPER NUMBER	
		1746		
DATE MAILED: 11/17/2005				

Please find below and/or attached an Office communication concerning this application or proceeding.

Office Action Summary	Application No.	Applicant(s)	
	10/707,081	KAO ET AL.	
	Examiner Michael Kornakov	Art Unit 1746	

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --

Period for Reply

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) OR THIRTY (30) DAYS, WHICHEVER IS LONGER, FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

Status

- 1) Responsive to communication(s) filed on 25 October 2005.
- 2a) This action is FINAL. 2b) This action is non-final.
- 3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

Disposition of Claims

- 4) Claim(s) 1-7 is/are pending in the application.
 - 4a) Of the above claim(s) _____ is/are withdrawn from consideration.
- 5) Claim(s) _____ is/are allowed.
- 6) Claim(s) 1-7 is/are rejected.
- 7) Claim(s) _____ is/are objected to.
- 8) Claim(s) _____ are subject to restriction and/or election requirement.

Application Papers

- 9) The specification is objected to by the Examiner.
- 10) The drawing(s) filed on 20 November 2003 is/are: a) accepted or b) objected to by the Examiner.
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).
- 11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.

Priority under 35 U.S.C. § 119

- 12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
 - a) All b) Some * c) None of:
 1. Certified copies of the priority documents have been received.
 2. Certified copies of the priority documents have been received in Application No. _____.
 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).

* See the attached detailed Office action for a list of the certified copies not received.

Attachment(s)

1) <input checked="" type="checkbox"/> Notice of References Cited (PTO-892)	4) <input type="checkbox"/> Interview Summary (PTO-413) Paper No(s)/Mail Date. _____.
2) <input type="checkbox"/> Notice of Draftsperson's Patent Drawing Review (PTO-948)	5) <input type="checkbox"/> Notice of Informal Patent Application (PTO-152)
3) <input type="checkbox"/> Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date _____.	6) <input type="checkbox"/> Other: _____.

DETAILED ACTION

1. Claims 8-15 are cancelled by Applicants' amendment of October 25, 2005.
2. Claims 1-7 are pending.

Claim Rejections - 35 USC § 102

3. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless –

(a) the invention was known or used by others in this country, or patented or described in a printed publication in this or a foreign country, before the invention thereof by the applicant for a patent.

(e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

The applied reference has a common inventor with the instant application.

Based upon the earlier effective U.S. filing date of the reference, it constitutes prior art under 35 U.S.C. 102(e). This rejection under 35 U.S.C. 102(e) might be overcome either by a showing under 37 CFR 1.132 that any invention disclosed but not claimed in

the reference was derived from the inventor of this application and is thus not the invention "by another," or by an appropriate showing under 37 CFR 1.131.

4. Claims 1-4 are rejected under 35 U.S.C. 102(a) or 102(e) as being anticipated by Chen et al (US 2003/0116534).

A method of cleaning a substrate with a surface covered by a patterned metal layer (conductive layer) and a patterned resist layer (dielectric layer) *in order* is provided, subsequently, oxygen-plasma ashing is performed to remove the patterned resist layer to expose the surface of the patterned metal layer. (reads on forming an opening in the dielectric layer to expose the portion of conductive layer). The surface of the patterned metal layer is cleaned with sulfuric peroxide, ***molar concentration of sulfuric acid and hydrogen peroxide therein being 0.07M.about.0.4M and 0.8M.about.1.5M***, respectively in deionized water. In addition, the temperature of the sulfuric peroxide during cleaning is 25° C to about 50° C, preferably 34° C (see abstract, Fig. 1, 0015, 0019, claim 16).

5. Claims 1 and 6 are rejected under 35 U.S.C. 102(b) as being anticipated by Daubenspeck et al (US 20020045332).

Disclosed is a dual damascene process for fabricating a semiconductor device (abstract, 0045,0049), wherein the before forming a dual damascene structure, the dielectric layer is on top of a conductive layer, then subjecting the exposed damascene to a cleaning procedure by using a mixture of sulfuric acid and hydrogen peroxide in water (0042, 0054, Fig.8 and 9).

Claim Rejections - 35 USC § 103

6. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

7. The factual inquiries set forth in *Graham v. John Deere Co.*, 383 U.S. 1, 148 USPQ 459 (1966), that are applied for establishing a background for determining obviousness under 35 U.S.C. 103(a) are summarized as follows:

1. Determining the scope and contents of the prior art.
2. Ascertaining the differences between the prior art and the claims at issue.
3. Resolving the level of ordinary skill in the pertinent art.
4. Considering objective evidence present in the application indicating obviousness or nonobviousness.

8. This application currently names joint inventors. In considering patentability of the claims under 35 U.S.C. 103(a), the examiner presumes that the subject matter of the various claims was commonly owned at the time any inventions covered therein were made absent any evidence to the contrary. Applicant is advised of the obligation under 37 CFR 1.56 to point out the inventor and invention dates of each claim that was not commonly owned at the time a later invention was made in order for the examiner to consider the applicability of 35 U.S.C. 103(c) and potential 35 U.S.C. 102(e), (f) or (g) prior art under 35 U.S.C. 103(a).

Art Unit: 1746

9. Claim 5 is rejected under 35 U.S.C. 103(a) as being unpatentable over Chen or over Daubenspeck.

Chen and Daubenspeck do not specify the duration of treatment with the mixture of sulfuric acid and hydrogen peroxide, however, Chen and Daubenspeck state that the composition is used to completely remove polymer, and prevent the damage to metal, thus acknowledging that the time of treatment is a result effective variable, and, therefore, as *In re Boesch and Slaney* 205 USPQ 215 (CCPA 1980), the discovery of optimum value of result effective variable in known process is ordinarily within the skill in the art and would have been obvious.

10. Claim 7 is rejected under 35 U.S.C. 103(a) as being unpatentable over either Chen or Daubenspeck, each one individually in view of Yates (US 20040157448).

Both Daubenspeck and Chen disclose the process as instantly claimed using the cleaning composition as claimed. They are silent about the structure of a conductive layer, as specified in claim 7.

Yates discloses a method and a composition for cleaning etch residues. As shown in FIG. 4, structure 50 includes a first layer 53, which is an adhesive layer that includes titanium metal, a second layer 54, which is an antireflective layer that includes titanium nitride, a third layer 55, which is a digit line or any conductive layer that includes an aluminum/copper alloy, a fourth layer 56, which is an antireflective layer that includes titanium nitride, and a fifth layer 57, which is a dielectric layer that includes silicon oxides. A cleaning composition of the present invention is advantageously used to clean the structure 50 to remove etch residue without significantly damaging the

underlying layers of material, particularly the aluminum/copper alloy layer 55. Other references cited in PTOL-892 and not used in the present rejection also show the sandwiched structure of layers as claimed is a conventional arrangement in fabrication of semiconductor devices. Since no criticality is shown for applying the instantly claimed process particularly to the structure of claim 7, it would have been obvious to those skilled in the art at the time the invention was made to apply the cleaning method and cleaning composition of Chen or Daubenspeck to an arrangement that includes the conventionally used arrangement of layers as per Yates, as a mere design choice, and with the reasonable expectation of success.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Michael Kornakov whose telephone number is (571) 272-1303. The examiner can normally be reached on 9:00am - 5:30pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Michael Barr can be reached on (571) 272-1414. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Application/Control Number: 10/707,081
Art Unit: 1746

Page 7

M. Kornakov

Michael Kornakov
Primary Examiner
Art Unit 1746

11/10/2005